

IN THE UNITED STATES PATENT AND TRADEMARK OFFICE

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In re Application of:

Bencher, et al.

Serial No.: 10/684,079

Confirmation No.: Unknown

Filed:

October 9, 2003

For:

A Silicon Carbide

Deposition For Use As A Low Dielectric Constant Anti-Reflective Coating Group Art Unit: Unknown

Examiner:

Unknown

Commissioner for Patents P.O. Box 1450 Alexandria, VA 22313-1450

Dear Sir:

CERTIFICATE OF MAILING 37 CFR 1.8

I hereby certify that this correspondence is being deposited on <u>January 23, 2004</u> with the United States Postal Service as First Class Mail in an envelope addressed to: Commissioner for Patents, P.O. Box 1450 Alexandria, VA 22313-1450.

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Signature

INFORMATION DISCLOSURE STATEMENT

The Applicants, and the Attorney who signs below on the basis of the information supplied by the inventor and the information in his file, submit herewith patents, publications, or other information of which they are aware, which may be material to the examination of this application and in respect of which there may be a duty to disclose in accordance with 37 CFR § 1.56.

While the information submitted in this Information Disclosure Statement may be material pursuant to 37 CFR § 1.56, it is not intended to constitute an admission that any patent, publication, or other information referred to therein is prior art for this invention unless specifically designated as such.

In accordance with 37 CFR § 1.97, this Information Disclosure Statement is not to be construed as a representation that a search has been made or that no other possibly material information as defined under 37 CFR § 1.56(a) exists.

The patents and/or publications submitted herewith are set forth on the attached Form PTO-1449.

If the sum of \$180.00 is due under 37 CFR § 1.17(p) pursuant to § 1.97, the Commissioner is hereby authorized to charge this fee, and any other fee necessary to make this submission timely, to the Deposit Account No.. 20-0782/AMAT/2966.C1/BKH.

Respectfully submitted,

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U.S. Department of Commerce, Patent and Trademark Office				Docket No.		Serial No.		
(PTO Form 1449 modified)					AMAT/2966.C1/DSM /BCVD/JW		10/684,079	
INFORMAT	SCLOSURE STA	Applicant Bencher, et al.		Confirmation No. Unknown				
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	U.S. Patent Documents					2003	Unknown	
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